

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Hirayama et al.
Appl. No.	:	10/590,046
Filed	:	June 15, 2007
For:	:	BASE MATERIAL FOR PATTERN-FORMING MATERIAL, POSITIVE RESIST COMPOSITION AND METHOD OF RESIST PATTERN FORMATION
Examiner	:	Johnson, C.
Group Art Unit	:	1795

SUBMISSION WITH RCE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **April 24, 2009**, please amend the above-referenced application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 8 of this paper.